

Contents

Preface — V

1 Introduction — 1

- 1.1 Analytical parameters — 1
 - 1.1.1 Define what is to be measured? — 1
 - 1.1.2 How important is this analysis? — 2
 - 1.1.3 What is the sample, how is it sampled and how does it get to the lab? — 2
 - 1.1.4 Accuracy — 2
 - 1.1.5 Precision — 3
 - 1.1.6 Sensitivity — 3
 - 1.1.7 Limit of detection — 4
 - 1.1.8 Time of analysis — 4
 - 1.1.9 Importance of the results — 5
 - 1.1.10 What spectrometric technique is to be used? — 5
 - 1.1.11 What sample preparation is required? — 7
 - 1.1.12 Available resources — 9
 - 1.1.13 Reporting and post-analysis actions — 9
- 1.2 Reference materials — 10
- 1.3 Validation — 12

Gerhard Schlemmer

2 Atomic absorption spectrometry and atomic fluorescence spectrometry — 14

- 2.1 Basic principles of atomic absorption spectrometry and atomic fluorescence spectrometry — 14
 - 2.1.1 Interaction of photons with electrons — 14
 - 2.1.2 Line width of absorbing atoms — 15
 - 2.1.3 Line width of emitting atoms in the source — 17
 - 2.1.4 Absorption process — 17
 - 2.1.5 Flame optical emission spectroscopy — 19
 - 2.1.6 Atomic fluorescence — 20
- 2.2 Technical means to facilitate AAS and AFS — 22
 - 2.2.1 General layout — 22
 - 2.2.2 Radiation source — 23
 - 2.2.3 Photometer and spectrometer — 30
 - 2.2.4 Counting photons and transfer to electrical information: Principle way of operation and criteria for optimal use — 35
 - 2.2.5 Zero absorption: technical means to define the baseline — 38
 - 2.2.6 Separation of specific and nonspecific absorption — 41

2.2.7	Sample introduction and principles of atom generation in AAS — 51
2.3	Physicochemistry outside and inside the atomizer — 64
2.3.1	Flames — 64
2.3.2	Graphite furnace — 69
2.3.3	Chemical vapor generation — 71
2.3.4	Atomic fluorescence — 73
2.4	Mastering the spectrometer and its accessories — 74
2.4.1	Figures of merit — 74
2.5	Mastering the application; instrument suitability; method development; estimation on expected working range, basics of method optimization for flame, furnace, CVG, cold vapor, cold vapor fluorescence. Special applications: coupling of methods. Analytical quality versus sample and element throughput — 90
2.5.1	Instrument performance verification — 90
2.5.2	Estimate of the expected working range — 93
2.5.3	Is the instrument suitable for the application? — 94
2.6	Typical applications in AAS and AFS — 104
2.6.1	Contaminated soils: An easy standard flame AAS application — 104
2.6.2	Geochemistry: The determination of refractory elements in refractory matrix — 106
2.6.3	Determinations in ultrapure materials: An unusual challenge — 107
2.6.4	Between liquid and solid: the direct analysis of clinical samples in GF-AAS — 114
2.6.5	Plants and other biological tissue: The way to fast GF-AAS determinations — 119
2.6.6	Element-matrix separation: The determination of As and Sb in water samples — 122
2.6.7	CVG with analyte trapping for ultra, ultra-traces — 124
2.6.8	The determination of mercury with the cold vapor technique and AFS — 126
	References — 130

José Luis Todolí

3	Inductively coupled plasma and microwave-induced plasma optical emission spectroscopy — 134
3.1	Introduction to inductively coupled plasma optical emission spectroscopy — 134
3.2	Plasma generation and fundamental parameters — 137
3.2.1	Characteristics of the ICP — 137
3.2.2	Mixed gas plasmas — 144
3.2.3	Generators — 145

3.3	Sample introduction systems — 146
3.3.1	Conventional liquid sample introduction system — 147
3.3.2	Drawbacks of conventional liquid sample introduction system — 151
3.3.3	Efficient nebulizers or spray chambers — 151
3.3.4	High solid nebulizers — 156
3.3.5	Cooled spray chambers — 158
3.3.6	Desolvation systems — 159
3.3.7	Low sample consumption systems — 162
3.3.8	Chemical vapor generation — 164
3.3.9	Electrothermal vaporization — 166
3.4	Torch configuration — 169
3.4.1	General characteristics — 169
3.4.2	Low argon consumption torches — 171
3.4.3	Plasma viewing mode — 172
3.5	Optical system — 174
3.5.1	Dispersive system — 176
3.5.2	Detectors — 178
3.6	General configurations — 181
3.7	Interferences in ICP-OES — 185
3.7.1	Spectroscopic interferences in ICP-OES — 186
3.7.2	Non-spectroscopic interferences (matrix effects) in ICP-OES — 189
3.7.3	Comparing spectroscopic and non-spectroscopic interferences — 202
3.8	Effect of the analyte chemical form — 202
3.9	Optimizing an ICP-OES system — 205
3.9.1	Optimization from the point of view of analytical figures of merit — 207
3.9.2	Optimization from the point of view of accuracy — 210
3.10	Methods for analyte quantification through ICP-OES — 215
3.11	Troubleshooting and maintenance in ICP-OES — 216
3.12	Microwave plasma optical emission spectroscopy — 219
3.12.1	Instrumentation in MWP-OES — 220
3.12.2	Matrix effects in MWP-OES — 224
3.12.3	Optimization in MWP-OES — 225
3.13	Comparison of ICP-OES, MIP-OES with other spectrochemical techniques — 226
3.14	Selected applications — 228
	Bibliography — 231

Lieve Balcaen

4	Inductively coupled plasma–mass spectrometry — 247
4.1	Introduction and brief history — 247
4.2	Instrumentation and principle of operation — 248
4.2.1	Sample introduction system — 249
4.2.2	Inductively coupled plasma ion source — 249
4.2.3	Extraction system — 250
4.2.4	Mass spectrometer — 252
4.2.5	Detectors — 262
4.2.6	Alternative sample introduction systems — 264
4.3	Spectral interferences — 266
4.3.1	Types of interferences — 267
4.3.2	Methods to tackle the problem of spectral interferences — 268
4.4	Nonspectral interferences — 275
4.4.1	Description of nonspectral interferences — 275
4.4.2	Methods to tackle the problem of nonspectral interferences — 277
4.5	Analytical performance — 279
4.6	Hyphenated ICP–MS — 282
4.7	Examples of typical applications — 283
4.7.1	(Ultra-)trace element determination — 284
4.7.2	Isotopic analysis — 284
4.7.3	Speciation analysis by means of LC–ICP–MS — 298
4.7.4	Spatially resolved analysis by means of LA–ICP–MS — 300
	References — 302

Michael W. Hinds

5	X-ray fluorescence spectrometry — 306
5.1	Overview — 306
5.1.1	What is X-ray fluorescence (XRF) spectrometry? — 306
5.1.2	What distinguishes XRF from other atomic spectrometric techniques? — 306
5.1.3	Types: Wavelength Dispersive XRF and Energy Dispersive XRF — 307
5.2	Physics of X-rays — 308
5.2.1	Introduction — 308
5.2.2	Characteristic fluorescence lines — 310
5.2.3	Absorption and fluorescence — 314
5.2.4	Generation of X-rays within the X-ray tube — 317
5.2.5	Production of fluorescence X-rays within the sample — 318
5.2.6	Infinite thickness and analysis depth — 319
5.2.7	Fluorescence yield — 320
5.3	WDXRF spectrometer and components — 320
5.3.1	X-ray tube — 322

5.3.2	Primary beam filters —	325
5.3.3	Atmosphere —	326
5.3.4	Sample cups and aperture —	326
5.3.5	Mask —	328
5.3.6	Collimators —	328
5.3.7	Crystals or analyzer crystals —	329
5.3.8	Goniometer —	331
5.3.9	Detectors —	331
5.3.10	Pulse height selection —	333
5.3.11	Auxiliary services —	336
5.3.12	Optimization of parameters —	336
5.4	EDXRF spectrometer and components —	337
5.4.1	X-ray sources —	338
5.4.2	Atmosphere —	339
5.4.3	Primary beam filters —	339
5.4.4	Sample cups and aperture —	340
5.4.5	Detectors —	340
5.4.6	Multichannel analyzer —	344
5.4.7	Auxiliary services —	344
5.4.8	Handheld EDXRF spectrometer —	345
5.4.9	Total reflection XRF —	346
5.4.10	Comparison between EDXRF and WDXRF —	346
5.5	Obtaining optimized net intensities and counting times —	347
5.5.1	Background corrected peaks WDXRF —	347
5.5.2	Background correction EDXRF —	350
5.5.3	Peak overlap corrections —	352
5.5.4	Measurement time —	354
5.6	Matrix effects specific to XRF —	356
5.6.1	Absorption —	357
5.6.2	Enhancement —	358
5.6.3	Particle size effects —	359
5.6.4	Mineralogical effects —	360
5.6.5	Chemical state effects —	361
5.7	Calibration and mathematical correction models —	362
5.7.1	Reference materials —	362
5.7.2	Matrix correction algorithms —	362
5.7.3	Calibration —	366
5.7.4	Validation —	367
5.7.5	Drift correction —	367
5.8	Universal calibration XRF analysis —	368
5.8.1	How it works —	369
5.8.2	Applications —	369

XII — Contents

5.8.3	Advantages and disadvantages —	369
5.9	Sample preparation —	370
5.9.1	Air sample preparation —	370
5.9.2	Liquid sample preparation —	370
5.9.3	Solid sample preparation —	372
5.10	Examples applications —	378
5.10.1	EDXRF – determination of Ag, As and Zn in lead concentrate —	378
5.10.2	WDXRF – Determination of Ag, Cu, and P in Sterling Silver —	381
5.11	Different applications and current trends in XRF —	385
5.11.1	Combination WDXRF and EDXRF in one instrument —	385
5.11.2	Microfocusing optics and element concentration mapping —	385
5.11.3	Layer thickness —	385
5.11.4	Vendor method packages —	386
5.11.5	Advances in EDXRF —	386
5.12	Concluding remarks —	386
5.13	Appendix —	387
5.13.1	Appendix 1: Table of photon energies of the principle K and L X-ray spectral lines —	387
5.13.2	Appendix 2: Table of K, L, and M X-ray excitation potentials of the elements —	390
5.13.3	Appendix 3: Table of mass attenuation coefficients for K α line energies of selected elements —	393
	References —	395

Index — 399